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제21회 한국반도체학술대회
February 24–26, 2014 / Hanyang University, Seoul, Korea

Q. Metrology, Inspection, and Yield Enhancement 분과

[WD4-Q] Metrology and Inspection

Date	Feb. 26, 2014 (Wed.)
Place	Room D / 제1공학관 402호 (# 402, Engineering Building I)

Session Chair: 유형원 수석(SK hynix), 김호섭 교수(선문대학교)

- WD4-Q-1 17:15-17:45**
WD4-Q-2 17:45-18:00 **Wafer Defect Inspection by Multi-Level Thresholding of SEM Images**
저자: Sunghyon Kim¹, Minwoo Kim², and Ilseok Oh^{1,2}
소속: ¹Department of Nano Technology, Chonbuk National University, ²Department of Computer Engineering Graduate School, Chonbuk National University
- WD4-Q-3 18:00-18:15** **저전압 TEM 측정을 이용한 그래핀 형상 및 결정립 관찰**
저자: 조영지^{1,3}, 양준모¹, Do Van Lam², 이승모², 김재현², 박윤창¹, 장지호³
소속: ¹나노융합기술원, ²한국기계연구원, ³한국해양대학교 응용과학과
- WD4-Q-4 18:15-18:30** **Accelerating Defect Inspection Technology by Next-Generation Inspection Platforms**
저자: Jeongho Ahn, Shijin Seong, Hyungseop Kim, Dong-Ryul Lee, Heewon Sunwoo, Dong-chul Ihm, and Soobok Chin
소속: Process Development Team, Semiconductor R&D Center, Samsung Electronics Co., Ltd.